



ALKALINE DETERGENT

DP188

Low Surface Tension Alkaline Detergent

VALTRON DP188 is a specially formulated high-purity alkaline detergent developed for removing polishing slurries and sub-micron particles from a wide range of substrates. DP188 detergent emulsifies the soil preventing re-deposition, and has excellent rinsability characteristics. The unique blend of anionic, nonionic and amphoteric surfactants in VALTRON DP188 coupled with a solvent provides efficient and effective contamination removal.

UNIQUE FEATURES

- Removes Hydrocarbon & Other Hydrophobic Soils
- Effective Penetration & Removal of Cerium Oxide & Other Polishing Slurries
- Unique Blend of Anionic, Nonionic & Amphoteric Surfactants
- Contains No Silicates, Biodegradable
- 0.2 Micron Filtration

APPLICATION

VALTRON DP188 detergent is effective in contact and non-contact cleaning equipment for ultrasonic, megasonic, immersion and mechanical scrub applications. The detergent is supplied in a liquid concentrate for dilution with deionized water. Typical dilution rates are 1.0 - 2.0% by volume, but may vary depending upon the type and quantity of contamination being removed.

PACKAGING

VALTRON DP188 detergent is available in 5 gallon (18.9 L) pails and 55 gallon (208 L) drums.



Photo courtesy of Branson Ultrasonics

TYPICAL PHYSICAL PROPERTIES

Appearance	Clear amber liquid
Specific Gravity 60°F (15.6°C) g/cc	1.028
pH (concentrate)	10.4
(1.0% solution, v/v)	9.8
Cloud Point (1.0% solution, v/v)	158°F (70°C)
Surface Tension (1.0% solution, v/v)	25.7 dynes/cm



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